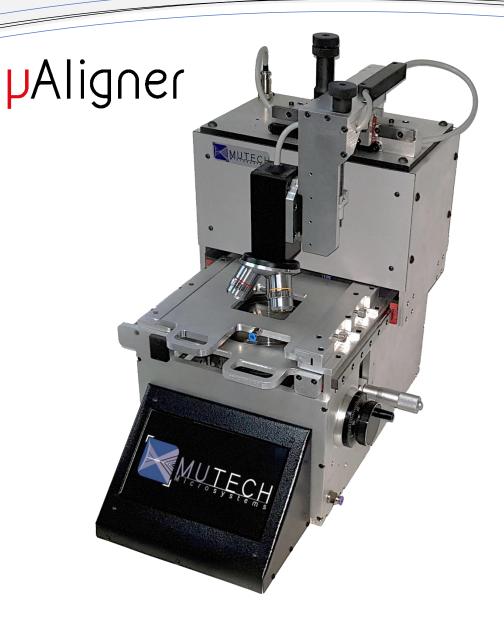


Features

- 365nm Wavelength
- Long life cold LED source
 with no warm up
- Dual microscope option
- Very low divergence and high homogeneity
- Full hd calibrated digital microscope with 590nm coaxial yellow illumination
- Electronic wafer pressure and gap control
- Micrometer based X-Y-R wafer aligning stage
- 7 inch capacitive touchscreen based control
- Up to 5 inch photomasks with interchangeable mask holders
- 100mm diameter UV aperture



Mutech microaligner

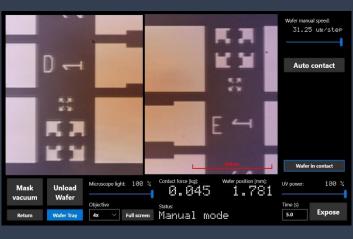
Mutech microsystems microAligner is a compact high value UV mask aligner designed for microfabrication applications.

It allows for easy fabrication of multilayer devices on a multitude of photoresists, with excellent exposure quality.

The easy to use, 7 inch touchscreen based control allows the user to align using the calibrated digital microscope and the X-Y-R micrometer based alignment stage.

The fully electronic wafer pressure and gap control allows for easy alignment and very high repeatability of the exposure conditions between processes.



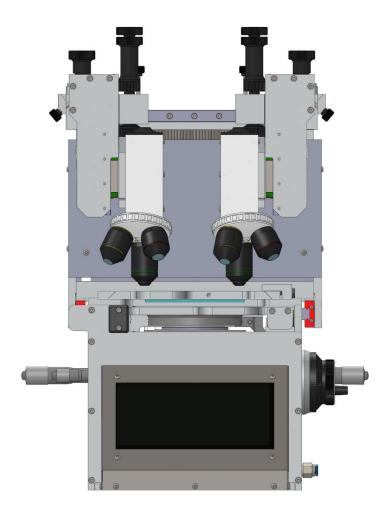


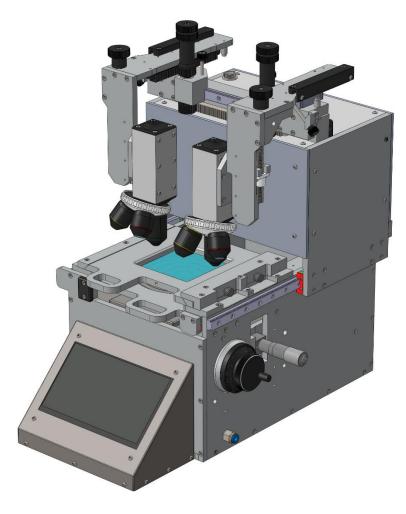
Dual microscope option for Mutech microAligner

We offer a dual microscope version of our mask aligner for rapid aligning of big photomasks.

Both microscopes have independent XYZ motion stages, allowing the operator to position them independently over the wafer.

The operator has access to both video feeds at the same time or any of the two on the screen while aligning, allowing the user to easily see two fiducial marks at once, simplifying the alignment process.







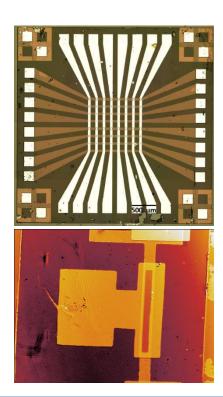
Main applications

The microAligner is ideal for the fabrication of high level systems for research applications. Main applications range from microfluidics, optics and biotechnology to microelectronic devices.

It provides the user with fast multilayer device fabrication capabilities thanks to its high resolution and high accuracy alignment.

LED source

The microAligner, compact mask aligner has very low maintenance requirements thanks to its LED based souce. It provides 365nm UV light with a very long life, no warmup times, instant turn on and no heat, with excellent homogeneity and low divergence.





7" Touchscreen

The microAligner is primarily controlled from its 7 inch capacitive touchscreen.

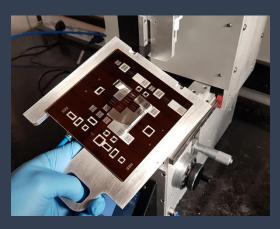
From here the user has access to all the controls of the machine, the microscope controls and video feed, exposure parameters, wafer stage controls and mask vacuum.

You have access to a real time wafer Z position and wafer pressure signals to allow for maximum repeatability.

User controls

The wafer Z position is controlled with a big 60mm rotary encoder for maximum control.

The user controls the wafer alignment to the mask using the X-Y-R stage with the mechanical micrometers. The microscope can be freely moved by the user around the photomask to look for alignment marks.





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Technical specifications

Mechanics		
X-Y-R Aligning stage		
Type of control	Mechanical, micrometer based	
Accuracy	1μm	
X-Y alignment span	6mm	
R alignment span	5°	
Z Wafer stage		
Type of control	Motorized	
Stage step	0.31μm/step	
Pressure sensing resolution	20g	
Maximum pressure	5kg	
60mm rotary encoder for precise gap/pressure control		
Wafer pressure sensing with live feedback for high repeatability between processes		
Interchangeable vacuum based photomask holders for 2",3",4",5" square photomasks and microscope slides		

UV Optics		
Wavelength	365nm	
Exposure time	0.1 - 200 s	
Exposure area	100mm diameter	
Power density	0.2 - 20 mW/cm^2	
Homogeneity	< 5%	
Light divergence	< 3°	
Motorized motion between aligning and		
exposure modes		

Microscope			
Camera resolution	1920x1080		
Auxiliary illumination	590nm coaxial yellow LED		
Field illumination mode	Clear field illumination		
Alignment technique	Top-side alignment, single camera		
Motion	3 axis, independent XYZ manual stage for each microscope		
Included objectives			
Objective	Effective magnification on screen		
Low mag	90x		
Medium mag	315x		
High mag	480x		

Electronics			
Display	7" full color LCD		
User control	Capacitive touchscreen for machine controls and microscope.		
32 Bits ARM cortex based integrated computer for maximum compactness			

Dimensions		
Size	350x490x470 mm	
Weight	19kg	
Power	110v/220v 250W	

Combine it with our direct laser system for maximum capabilities

Our direct laser lithography system, the microLaser, allows the user to fabricate its own optical masks, offering an increased versatility.

The microAligner system, as a complementary tool of the microLaser, offers the possibility to work with 365 nm sensitive photoresists and high accuracy alignment capabilities to obtain high aspect ratio structures and a high throughput on the lithography process.

These possibilities make the microAligner and microLaser package the ultimate solution for the fast fabrication and development of multilayered device applications including biomedical, microfluidics and microelectronic devices.